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(to be used for all correspondence after initial filing)

Application Number	10/642,305
Filing Date	August 18, 2003
First Named Inventor	Hongyong ZHANG et al.
Group Art Unit	2811
Examiner Name	Douglas W. Owens
Attorney Docket Number	740756-2646

Total Number of Pages in This Submission		Attorney Docket Number	740756-2646	
	ENCLOSU	RES (check all that apply)		
Fee Transmittal Form  Fee Attached  Amendment / Reply  After Final  Affidavits/declaration(s)  Extension of Time Request  Express Abandonment Request  Information Disclosure Statement  Certified Copy of Priority Document(s)  Response to Missing Parts/ Incomplete Application  Response to Missing Parts under 37 CFR 1.52 or 1.53	Assignm  for an A  Drawing  Declarat  Licensin  Petition  Applicat  Power of Change of Termina  Request	nent Papers Application) g(s) tion and Power of Attorney ng-related Papers to Convert to a Provisional	After Allowance Communication to Appeal Communication to Appeals and Interferences Appeal Communication to (Appeal Notice, Brief, Reply Brief) Proprietary Information Status Letter Application Data Sheet Request for Corrected Filing Enclosures A self-addressed prepaid packnowledging receipt Other Enclosure(s) (please	Board of Group  ng Receipt with oostcard for
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Firm or Individual name  Jeffrey L. 0 Nixon Peal 401 9 <sup>th</sup> Stre Suite 900 Washingto	body LLP eet, N.W.	neg. No. 35,483		
Signature	1 Cont			
Date March 2, 2	007			
CERTIFICATE Of I hereby certify that this correspondence  ☐ deposited with the United State class mail in an envelope addres Alexandria, VA 22313-1450  ☑ transmitted by facsimile on the (571) 273-8300  March 2, 2007	e is being: es Postal Ser essed to: Ma	ail Stop <u>·     </u> , Cor	elow with sufficient posta missioner for Patents, P. (	O. Box 1450,
Date		December Description	Signature	<del></del>
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#### IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:	)	
Hongyong ZHANG et al.	)	Examiner: Douglas W. Owens
Serial No. 10/642,305	)	Group Art Unit: 2811
Filed: August 18, 2003	)	-
For: THIN-FILM TRANSISTOR	)	
	)	

### INFORMATION DISCLOSURE STATEMENT

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In accordance with the duty of disclosure as set forth in 37 C.F.R. §1.56, Applicants hereby submit the following information in conformance with 37 C.F.R. §§ 1.97 and 1.98. Pursuant to 37 C.F.R. § 1.98, a copy of each of the documents cited is enclosed.

It is requested that the accompanying PTO-1449 be considered and made of record in the above-identified application. To assist the Examiner, the documents are listed on the attached form PTO-1449. It is respectfully requested that an Examiner initial a copy of this form be returned to the undersigned.

Applicants have filed Information Disclosure Statements on March 30, 2005; August 12, 2005; September 16, 2005; February 3, 2006; and June 1, 2006 to submit information from a pending litigation, namely, Case No. CV 04-4783 TJX (AJW). The litigation involves U.S. Patent No. 6,177,302 and U.S. Patent No. 6,566,175 which are in the same family as co-pending application Serial No. 10/408,891. The '891 application is not in the same family as the instant application. Further, the litigation involves U.S. Patent No. 5,532,291 which is not in the same family as the instant application. Moreover, the litigation involves U.S. Patent Nos. 5,313,075 and 6,607,947 which are in the same family as the instant application, as previously noted, and pending U.S. Application No. 10/401,891. The documents cited herein relate to this litigation.

03/05/2007 MAHMED1 88088099 192380 10642385 01 FC:1886 188.00 DA Sheet 1-1 (List 1) relates to documents from the above noted litigation. Sheets 1-5 (List 2-3) relates to document which were attached to Document Nos. 7 and 8 from Sheet 1-1.

Except for issue fees payable under 37 C.F.R. § 1.18, the Commissioner is hereby authorized by this paper to charge any additional fees during the entire pendency of this application including fees due under 37 C.F.R. §§ 1.16 and 1.17 which may be required, including any required extension of time fees, or credit any overpayment to Deposit Account No. 19-2380.

The Commissioner is hereby authorized to charge the Deposit Account No. 19-2380 in the amount of \$180 to comply with the provisions of 37 C.F.R. § 1.97(c).

The Commissioner is hereby authorized to charge any fees connected with this filing which may be required now, or credit any overpayment to Deposit Account No. 19-2380.

Respectfully submitted,

Meffrey I Coste

Registration No. 35,483

NIXON PEABODY LLP Suite 900 401 9<sup>th</sup> Street, N.W. Washington, DC 20004-2128

Telephone: (202) 585-8000

## FEE TRANSMITTAL FOR FY 2005

Patent fees are subject to annual revision.

Applicant claims small entity status. See 37 CFR 1.27

TOTAL AMOUNT OF PAYMENT (\$)180.00

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	Application Number	10/642,305	FIRE
	Filing Date	August 18, 2003	7011 6
	First Named Inventor	Hongyong ZHANG et al.	/ 32
	Examiner Name	Douglas W. Owens	MAR 0 2 2007
	Art Unit	2811	3 44
_	Attorney Docket No.	740756-2646	A. C.
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		1052	50	2052	25	Surcharge - late provisional filing fee or sheet	cover
Deposit		1053	130	1053	130	Non-English specification	
Account	Nixon Peabody LLP	1812	2,520	1812	2,520	For filing a request for ex parte reexamin	nation
Name		1804	920*	1804	920*	Requesting publication of SIR prior to Ex	
63	oner is authorized to: (check all that apply) s) indicated below  Credit any overpayments	1805	1,840*	1805	1,840*	action Requesting publication of SIR after Exar	miner
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	ified deposit account.	i .	450		225	Extension for reply within second month	
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1. BASIC FILE	ING FEE	1255	2,160	2255	1,080	Extension for reply within fifth month	
Large Entity	Small Entity	1401	500	2401	250	Notice of Appeal	
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1001 300	2001 150 Utility filing fee	1451	1,510	1451	1,510	Petition to institute a public use proceedi	ng
1002 200	2002 100 Design filing fee	1452	500	2452	250	Petition to revive - unavoidable	
1003 200	2003 100 Plant filing fee	1453	1,500	2453	750	Petition to revive - unintentional	
1004 300	2004 150 Reissue filing fee	1501	1,400	2501	700	Utility issue fee (or reissue)	
1005 200	2005 100 Provisional filing fee	1502	800	2502	400	Design issue fee	
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	SUBTOTAL (1) $(\$)$ 0	1460	130	1460	130	Petitions to the Commissioner	
	(4)	1807	50	1807	50	Processing fee under 37 CFR 1.17(q)	
2. EXTRA	CLAIM FEES FOR UTILITY AND REISSUE	1806	180	1806	180	Submission of Information Disclosure St	tmt \$180.00
	Fee from	8021	40	8021	40	Recording each patent assignment per pr	)
Total Claims	Extra Claims below Fee Paid  -20**= X = 0	1809	790	2809	395	(times number of properties) Filing a submission after final rejection	-
Independent	-3**= X = 0	1810	790	2810	395	(37 CFR 1.129(a)) For each additional invention to be exam	nined
Claims						(37 CFR 1.129(b))	
Multiple Depende	nt X = 0	1801	790	2801	395	Request for Continued Examination (RC	E)
Large Entity Fee Fee	Small Entity Fee Fee Fee Description	1802	900	1802	900	Request for expedited examination of a capplication	design
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Name (Print/Ty	pe) Jeffrey // Costellia	_	tration N nev/Ager		35,483	Telephone (202) 58	85-8000
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INFO	RMATION	DISC	LOSURE	Application Number	10/642,305
1				Filing Date	August 18, 2003
SIA	STATEMENT BY APPLICANT		First Named Inventor	Hongyong ZHANG et al.	
1	(use as many sheets	s as necess	eary)	Art Unit	2811
	,			Examiner Name	Douglas W. Owens
Sheet	1	of	5	Attorney Docket Number	740756-2646

	OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS						
Cite Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.)., date, page(s), volume-issue number(s), publisher, city and/or country where published.							
1	PERRIN, J. et al., "Mass-Spectrometric Study of NF3 Plasma-Etching of Silicon", Plasma Chemistry and Plasma Processing, Vol. 10, No. 4, (1990) pp. 571-587						
2	GROVE, A.S., "Physics and Technology of Semiconductor Devices", Wiley (New York), (1967), p. 334.						
3	GORDON, R. "Chemical Vapor Deposition of Coatings on Glass", Journal of Non- Crystalline Solids, Vol. 218, (1997), pp. 81-91.	-					
4	BALK, P. et al. "Phosphosilicate Glass Stabilization of FET Devices", Proceedings of the IEEE; Vol. 57, No. 9, (September 1969), pp.1558-1563.						
5	PLUMMER et al.; "Silicon VLSI Technology: Fundamentals, Practice and Modeling"						
6	NICOLLIAN, E.H. et al.; "MOS (Metal Oxide Semiconductor Physics and Technology", Wiley (New York) p. 774.						
7	Sze S.M. (Author ADAMS, A.C.), "VLSI Technology" Wiley, (New York) (1983) pp. 93-129.						
8	KRIEGLER, R.J, "Neutralization of Na+Ions in HC1-Grown Si0 <sub>2</sub> ", Applied Physics Letters, Vol. 20, No. 11, (June 1, 1972), pp. 449-541.						
9	DEAL, B.E. et al. "Chlorine Concentration Profiles in 0.2 -HCl and H <sub>2</sub> 0- HCl Thermal Silicon-Oxides Using Sims Measurements", Journal of the Electrochemical Society, Vol. 125, No. 12, (December 1978), pp. 2024-2027.						
10	ROHATGI, A. et al. "Sodium Passivation in HCl Oxide-Films on Si", Applied Physics Letters, Vol. 30, No. 2, (January 15, 1977) pp. 104-106.						
	No.1  1  2  3  4  5  6  7	No.¹ item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.  PERRIN, J. et al., "Mass-Spectrometric Study of NF3 Plasma-Etching of Silicon", Plasma Chemistry and Plasma Processing, Vol. 10, No. 4, (1990) pp. 571-587  GROVE, A.S., "Physics and Technology of Semiconductor Devices", Wiley (New York), (1967), p. 334.  GORDON, R. "Chemical Vapor Deposition of Coatings on Glass", Journal of Non-Crystalline Solids, Vol. 218, (1997), pp. 81-91.  BALK, P. et al. "Phosphosilicate Glass Stabilization of FET Devices", Proceedings of the IEEE; Vol. 57, No. 9, (September 1969), pp.1558-1563.  PLUMMER et al.; "Silicon VLSI Technology: Fundamentals, Practice and Modeling"  NICOLLIAN, E.H. et al.; "MOS (Metal Oxide Semiconductor Physics and Technology", Wiley (New York) p. 774.  Sze S.M. (Author ADAMS, A.C.), "VLSI Technology" Wiley, (New York) (1983) pp. 93-129.  KRIEGLER, R.J, "Neutralization of Na+Ions in HC1-Grown Si02", Applied Physics Letters, Vol. 20, No. 11, (June 1, 1972), pp. 449-541.  PEAL, B.E. et al. "Chlorine Concentration Profiles in 0.2 –HCl and H <sub>2</sub> 0- HCl Thermal Silicon-Oxides Using Sims Measurements", Journal of the Electrochemical Society, Vol. 125, No. 12, (December 1978), pp. 2024-2027.					

ı	Examiner	Date	
ı	Signature	Considered	

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>&</sup>lt;sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> See Kinds Codes of USPTO Patent Documents at <a href="https://www.uspto.gov">www.uspto.gov</a> or MPEP 901.04. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.

<sup>&</sup>lt;sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> Applicant is to place a check mark here if English language Translation is attached.

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(List 2-3)

Substitute for form 1449A/PTO				Complete if Known ADEM!		
INFORMATION DISCLOSURE		Application Number	10/642,305			
		Filing Date	August 18, 2003			
STATEMENT BY APPLICANT	First Named Inventor	Hongyong ZHANG et al.				
	(use as many sheets as necessary)			Art Unit	2811	
				Examiner Name	Douglas W. Owens	
Sheet	2	of	5	Attorney Docket Number	740756-2646	

		OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS						
Examiner Initials	Cite No.1							
		ROHATGI A,, et al. "Chlorine Incorporation in HCl Oxides", Journal of The Electrochemical Society, Vol. 126, No. 1, (January 1979), pp. 143-148.						
		ROHATGI A., et al. "Mobile Sodium Ion Passivation in HCl Oxides," Journal of the Electrochemical Society, Vol. 126, No. 1, (January 1979), pp. 149-154.						
		WILLIAMS, R. et al. "Mobile Fluoride Ions in SiO2", Journal of Applied Physics, Vol. 46, No. 2 (February 1975) pp. 695-698						
		LEE, M.K. et al. "Control of Silicon Dioxide Properties by RF Sputtering", Journal of the Electrochemical Society, Vol. 130, No. 3, (March 1983) pp. 685-859						
		DASILVA, E.F. et al. "Radiation Response of MOS Capacitors Containing Fluorinated Oxides, IEEE Transaction on Nuclear Science, Vol. 34, No. 6, (December 1987) pp. 1190-1195.						
		NISHIOKA, Y. et al. "Dramatic Improvement of Hot-Electron-Induced Interface Degradation in MOS Structures Containing F or C1 in Si0 <sub>2</sub> ", IEEE Electron Device Letters, Vol. 9, No. 1, (Jan. 1988), pp. 38-40.						
		NISHIOKA, Y. et al. "Dielectric Characteristics of Fluorinated Ultradry Si02" Applied Physics Letters, Vol. 54, No. 12, (March 20, 1989), pp. 1127-1129						
		NISHIOKA, Y. et al. "Hot-Electron Hardened Si-Gate MOSFET Utilizing F-Implantation", IEEE Electron Device Letters, Vol. 10, No. 4, (April 1989), pp. 141-143.						
		BRUNO, G. et al. "Study of the NF <sub>3</sub> Plasma Cleaning of Reactors for Amorphous-Silicon Deposition", Journal of Vacuum Science & Technology A, Vol. 12, No. 3, (1994), pp. 690-698						
		JANSEN, F. et al. "Contamination Effects in Glow-Discharge Deposition Systems",  Journal of Vacuum Science & Technology A, Vol. 6, No. 1, (1988), pp. 13-18						
Examiner Signature	Ή	Date Considered	I					

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>&</sup>lt;sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> See Kinds Codes of USPTO Patent Documents at <a href="www.uspto.gov">www.uspto.gov</a> or MPEP 901.04. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.

<sup>&</sup>lt;sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> Applicant is to place a check mark here if English language Translation is attached.

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Substitute	e for form 1449A/PTO			Complete if Known		
INFO	RMATION I	NICCI	OSHDE	Application Number	10/642,305	
	TEMENT BY			Filing Date	August 18, 2003	
51A				First Named Inventor	Hongyong ZHANG et al.	
	(use as many sheets o	as necesso	ury)	Art Unit	2811	
		_		Examiner Name	Douglas W. Owens	
Sheet	3	of	5	Attorney Docket Number	740756-2646	

	OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS						
Examiner Initials	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.)., date, page(s), volume-issue number(s), publisher, city and/or country where published.					
		KARULKAR, P.C. et al., "XPS AES Investigation of Cross Contamination in a Plasma Etcher", Journal of Vacuum Science & Technology B, Vol. 3, No. 3, (1985), pp. 889-891					
		Exhibit 7, Asserted Claim Chart - Sano Reference, JP 64-35959					
		FRANCOIS-SAINT-CYR, et al. "Diffusion of 18 elements implanted into thermally grown Si0 <sub>2</sub> ", Journal of Applied Physics, Vol. 94, No. 12, (December 15, 2003), pp. 7433-7439					
		DATAR, S.A. et al. "AMS Studies of the Diffusion of Chlorine in Silicon-Wafers"  Nuclear Instruments & Methods in Physics Research- B 99 - Beam Interactions with  Materials and Atoms, (1995), pp. 549-552					
		TSENG, H.H. et al. "Fluorine Diffusion on a Polysilicon Grain-Boundary Network in Relation to Boron Penetration from P+ Gates", IEEE Electron Device Letters, Vol. 13, No. 1, (January 1992), pp. 14-16					
•		TROXELL, JOHN R. et al. "Polycrystalline Silicon Thin-Film Transistors on a Novel 800°C Glass Substrate", IEEE Electron Device Letters, Vol. 7, No. 11, (November 1986), pp. 597-599					
		ERMOLIEFF, A. et al. "XPS Studies of Contamination of Reactor and Silicon Surfaces Caused by Reactive Ion Etching", Semiconductor Science and Technology, Vol. 6, (1991), pp. 290-295					
		ERMOLIEFF, A. et al. "X-Ray Photoelectron-Spectroscopy Studies of Contamination and Cleaning of Surfaces Exposed to a Flurocarbon Plasma", Journal of Vacuum Science & Technology A, Vol. 9, No. 6, (November/December 1991), pp. 2900-2906					

Examiner	 Date		
Signature	Considered	1	

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>&</sup>lt;sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> See Kinds Codes of USPTO Patent Documents at <a href="www.uspto.gov">www.uspto.gov</a> or MPEP 901.04. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.

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•					MAR 02 2007 8	
Substitute for form 1449A/PTO				Complete if Known		
INFO	RMATION I	nisci	ACHDE	Application Number	10/642,305	
				Filing Date	August 18, 2003	
STATEMENT BY APPLICANT (use as many sheets as necessary)				First Named Inventor	Hongyong ZHANG et al.	
			(ניצו)	Art Unit	2811	
				Examiner Name	Douglas W. Owens	
Sheet	4	of	5	Attorney Docket Number	740756-2646	

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS					
Examiner Initials*	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.)., date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>		
		HUGHES, C. et al. "In-situ HDP-CVD Process Diagnostics Based on Quadrupole Mass Spectrometry", (IMEC Leuven, Belgium)			
		IQBAL, Z. et al. "Raman scattering from hydrogenated microcrystalline and amorphous silicon", J. Phys. C. Solid State Phys., Vol. 15 (1982) pp. 377-392			
· · · ·		JENG, S.P. et al. "Anomalous Diffusion of Fluorine in Silicon", Applied Physics Letters, Vol. 61, No. 11, (September 14, 1992), pp. 1310-1312			
		YOUNG, N.D. et al. "Mobile ion instabilities in polycrystalline silicon thin film transistors" Applied Surface Science, Vol. 39, (1989), pp. 364-367			
		SAMESHIMA et al. "XeCl Excimer Annealing Used to Fabricate Poly-Si TFT's", IEEE Electronic Device Letters, Vol. 7, No. 5, (May 1986), pp. 276-278			
		KAKKAD et al. "Crystallized Si films by low-temperature rapid thermal annealing of amorphous silicon", J. Applied Physics, Vol. 65, No. 5, (March 1, 1989), pp, 2069-2072			
		PINARBASI, M. et al., "Hydrogenated Amorphous Silicon Films Deposited by DC Planar Magnetron Reactive Sputtering", Superlattices and Microstructure, Vol. 3, No. 4, (1987) pp. 331-340			
		MADAN, A. et al. "Characterization of Schottky Barriers", The Physics and Applications of Amorphous Semiconductors, Academic Press, pp. 193-197			
		MADAN et al. "Use of PECVD System in Thin Film Technology", Workshop on Industrial Plasma Applications, pp. 1-10			
		MALEY, N. et al. "Infrared absorption and thermal evolution study and hydrogen bonding in a-SiH", Journal of Vacuum Science & Technology, Vol. 7, No. 3, (May/June 1989), pp. 1267-1270			

Examiner	Date	
Signature	Considered	

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			U.S. PATENT DOCUM	IENTS	
Examiner Initials	Cite No.	U.S. Patent Document	Publication Date	Name of Patentee or	Pages, Columns, Lines, Where
		Number - Kind Code <sup>2</sup> (if known)	MM-DD-YYYY	Applicant of Cited Document	Relevant Passages or Relevant Figures Appear
		US-4,007,294	02/08/1977	Woods et al.	
		US-4,485,146	11/27/1984	Mizuhashi et al.	
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Examiner Initials	Cite No. <sup>1</sup>	Foreign Patent Document  Kind Code <sup>3</sup> Country Code <sup>3</sup> Number <sup>4</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Application of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T⁵
		JP 64-35959	02/07/1989			
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	•	OTHER PRIOR A	ART – NON PATENT L	ITERATURE DOCUMENTS	•	
Examiner Cite Include name of the author (in CAPITAL LETTERS), title of the article (when a item (book, magazine, journal, serial, symposium, catalog, etc.)., date, page(s), vous publisher, city and/or country where published.				catalog, etc.)., date, page(s), volum		T <sup>2</sup>
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Examiner	Date
Signature	Considered

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>&</sup>lt;sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> See Kinds Codes of USPTO Patent Documents at <a href="https://www.uspto.gov">www.uspto.gov</a> or MPEP 901.04. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.

<sup>&</sup>lt;sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> Applicant is to place a check mark here if English language Translation is attached.

(List 1)

Application Number

INFORMATION DISCLOSURE TATEMENT BY APPLICANT

sbstitute for form 1449A/PTO

(use as many sheets as necessary)

August 18, 2003 Filing Date Hongyong ZHANG et al. First Named Inventor 2811 Art Unit Douglas W. Owens **Examiner Name** 

Complete if Known

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Sheet 1 of 1 Attorney Docket Number 740756-2646

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS							
Examiner Initials*	Cite No.1						
	1	Toppoly's Opposition Claim Construction Brief, May 30, 2006					
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	3	Plaintiff and Counterclaim Defendant Semiconductor Energy Laboratory Co., Ltd.'s Memorandum of Points and Authorities in Opposition to Defendants' and Counterclaim Plaintiffs' Claim Construction Brief (signed on 05/26/2006), May 30, 2006					
	4	Supplemental Declaration of Reginald J. Hill in Support of Semiconductor Energy Laboratory Co., Ltd.'s Claim Constructions (signed on 05/26/2006), May 30, 2006					
	5 .	Toppoly Optoelectronics Corp.'s Supplemental Response to Semiconductor Energy Laboratory Co., Ltd.'s Interrogatory No. 4, June 21, 2006					
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Signature	Considered

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